AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

- (Original) An adhesive sheet, comprising a polymer component,
 the breaking strength of the adhesive sheet in a B-stage state being from 0.1 to
 MPa at 25°C, and the breaking elongation thereof being from 1 to 40% at 25°C.
- 2. (Original) An adhesive sheet, comprising a polymer component, the elastic modulus of the adhesive sheet in a B-stage state being from 1 to 3000 MPa in measurement of the dynamic viscoelasticity at 25°C and 10 Hz, and the elastic modulus thereof being from 4000 to 20000 MPa in measurement of the dynamic viscoelasticity at 25°C and 900 Hz.
- 3. (Original) An adhesive sheet, comprising a polymer component, the elastic modulus of the adhesive sheet in a B-stage state being from 1 to 3000 MPa in measurement of the dynamic viscoelasticity at 25°C and 10 Hz, and the elastic modulus thereof being from 4000 to 20000 MPa in measurement of the dynamic viscoelasticity at -20°C and 10 Hz.
- 4. (Currently amended) The adhesive sheet according to claim 2-or-3, comprising the polymer component, and

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. the elastic modulus of the adhesive sheet in a B-stage state being from 0.1 to 20 MPa in measurement of the dynamic viscoelasticity at 60°C and 10 Hz.

5. (Currently amended) The adhesive sheet according to <u>claimany one of</u> claims 2-to 4, comprising the polymer component,

the breaking strength of the adhesive sheet in a B-stage state being from 0.1 to 10 MPa at 25°C, and the breaking elongation thereof being from 1 to 40% at 25°C.

- 6. (Currently amended) The adhesive sheet according to <u>claimany one of claims 1 to 5</u>, wherein the polymer component has a glass transition temperature of -30 to 50°C, and a weight-average molecular weight of 50000 to 1000000.
- 7. (Original) The adhesive sheet according to claim 6, wherein the polymer component, which has a glass transition temperature of -30 to 50°C and a weight-average molecular weight of 50000 to 1000000, is contained in an amount of 50% or less of the total weight of the adhesive sheet from which the weight of a filler is removed.
- 8. (Original) The adhesive sheet according to claim 7, further comprising a thermosetting component.
- 9. (Currently amended) The adhesive sheet according to claim 7-or-8, further comprising 5 to 70% by weight of the filler.

- 10. (Currently amended) The adhesive sheet according to <u>claimany one of claims 1 to 9</u>, wherein the content of remaining volatile matters is from 0.01 to 3% by weight.
- 11. (Currently amended) The adhesive sheet according to <u>claimany one of claims 1-to 10</u>, which has a film thickness of 1 to 250 μ m.
- 12. (Currently amended) A dicing tape integrated type adhesive sheet formed by lamination of the adhesive sheet according to <u>claimany one of claims</u> 1 to 11 and a dicing tape.
- 13. (Currently amended) A method of producing a semiconductor device, comprising:
- I) the step of sticking the adhesive sheet according to <u>claim</u>any one of claims 1 to 11 onto a semiconductor wafer,
 - II) the step of rendering the semiconductor wafer permissible to be cut,
- III) the step of sticking a dicing tape onto the adhesive sheet in order of I-II-III, II-III, or I-III-II, and further comprising:
- IV) the step of cutting the semiconductor wafer and the adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and
- V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.

14. (Original) A method of producing a semiconductor device, comprising:

I') the step of sticking the dicing tape integrated type adhesive sheet according to claim 12 onto a semiconductor wafer, and

II) the step of rendering the semiconductor wafer permissible to be cut in order of I'-II or II-I', and further comprising:

IV) the step of cutting the semiconductor wafer and the adhesive sheet of the dicing tape integrated type adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and

V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.

- 15. (Currently amended) The method of producing a semiconductor device according to claim 13-or-14, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.
- 16. (New) The adhesive sheet according to claim 3, comprising the polymer component, and

the elastic modulus of the adhesive sheet in a B-stage state being from 0.1 to 20 MPa in measurement of the dynamic viscoelasticity at 60°C and 10 Hz.

17. (New) The adhesive sheet according to claim 3, comprising the polymer component,

the breaking strength of the adhesive sheet in a B-stage state being from 0.1 to 10 MPa at 25°C, and the breaking elongation thereof being from 1 to 40% at 25°C.

- 18. (New) The adhesive sheet according to claim 2, wherein the polymer component has a glass transition temperature of -30 to 50°C, and a weight-average molecular weight of 50000 to 1000000.
- 19. (New) The adhesive sheet according to claim 18, wherein the polymer component, which has a glass transition temperature of -30 to 50°C and a weight-average molecular weight of 50000 to 1000000, is contained in an amount of 50% or less of the total weight of the adhesive sheet from which the weight of a filler is removed.
- 20. (New) The adhesive sheet according to claim 19, further comprising a thermosetting component.
- 21. (New) The adhesive sheet according to claim 20, further comprising 5 to 70% by weight of the filler.
- 22. (New) The adhesive sheet according to claim 3, wherein the polymer component has a glass transition temperature of -30 to 50°C, and a weight-average molecular weight of 50000 to 1000000.

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- 23. (New) The adhesive sheet according to claim 22, wherein the polymer component, which has a glass transition temperature of -30 to 50°C and a weight-average molecular weight of 50000 to 1000000, is contained in an amount of 50% or less of the total weight of the adhesive sheet from which the weight of a filler is removed.
- 24. (New) The adhesive sheet according to claim 23, further comprising a thermosetting component.
- 25. (New) The adhesive sheet according to claim 24, further comprising 5 to 70% by weight of the filler.
- 26. (New) The adhesive sheet according to claim 2, wherein the content of remaining volatile matters is from 0.01 to 3% by weight.
- 27. (New) The adhesive sheet according to claim 3, wherein the content of remaining volatile matters is from 0.01 to 3% by weight.
- 28. (New) The adhesive sheet according to claim 2, which has a film thickness of 1 to 250 μm .
- 29. (New) The adhesive sheet according to claim 3, which has a film thickness of 1 to 250 μm .

- 30. (New) A dicing tape integrated type adhesive sheet formed by lamination of the adhesive sheet according to claim 2 and a dicing tape.
- 31. (New) A dicing tape integrated type adhesive sheet formed by lamination of the adhesive sheet according to claim 3 and a dicing tape.
 - 32. (New) A method of producing a semiconductor device, comprising:
- the step of sticking the adhesive sheet according to claim 2 onto a semiconductor wafer,
 - II) the step of rendering the semiconductor wafer permissible to be cut,
- III) the step of sticking a dicing tape onto the adhesive sheet in order of I-II-III, II-III, or I-III-II, and further comprising:
- IV) the step of cutting the semiconductor wafer and the adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and
- V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.
- 33. (New) The method of producing a semiconductor device according to claim 32, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.
 - 34. (New) A method of producing a semiconductor device, comprising:

- the step of sticking the adhesive sheet according to claim 3 onto a semiconductor wafer,
 - II) the step of rendering the semiconductor wafer permissible to be cut,
- III) the step of sticking a dicing tape onto the adhesive sheet in order of I-II-III, II-III, or I-III-II, and further comprising:
- IV) the step of cutting the semiconductor wafer and the adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and
- V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.
- 35. (New) The method of producing a semiconductor device according to claim 34, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.
- 36. (New) The method of producing a semiconductor device according to claim 14, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.
 - 37. (New) A method of producing a semiconductor device, comprising:
- I') the step of sticking the dicing tape integrated type adhesive sheet according to claim 30 onto a semiconductor wafer, and
- II) the step of rendering the semiconductor wafer permissible to be cut in order of l'-II or II-I', and further comprising:

- IV) the step of cutting the semiconductor wafer and the adhesive sheet of the dicing tape integrated type adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and
- V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.
- 38. (New) The method of producing a semiconductor device according to claim 37, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.
 - 39. (New) A method of producing a semiconductor device, comprising:
- I') the step of sticking the dicing tape integrated type adhesive sheet according to claim 31 onto a semiconductor wafer, and
- II) the step of rendering the semiconductor wafer permissible to be cut in order of l'-II or II-I', and further comprising:
- IV) the step of cutting the semiconductor wafer and the adhesive sheet of the dicing tape integrated type adhesive sheet, thereby yielding adhesive-sheet-stuck semiconductor chips which are individual pieces, and
- V) the step of bonding the adhesive-sheet-stuck semiconductor chips onto a semiconductor-chip-mounting support member.

40. (New) The method of producing a semiconductor device according to claim 39, wherein a method for rendering the semiconductor wafer permissible to be cut is half cut dicing or stealth dicing.